

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1525889	trench\$3 or recess\$3 or groove\$1 or depression\$1	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:06
L2	178725	implant\$3	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:06
L3	380673	etch\$3	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:06
L4	1207892	semiconduct\$3 or silicon	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:06
L5	60462	3 with 1	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:07
L6	9399	1 with 2	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:07
L7	3391566	(well\$1 or tub\$1)	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:07
L8	595782	(anneal\$3 or heat\$3 or thermal\$3) same 7	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:08
L9	44568	2 same 7	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:08
L10	117821	(oxidiz\$3 or oxidation) with (oxide or dioxide or sio2 or "sio.sub.2")	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:08
L11	192125	nitride or "si.sub.3 n.sub.4" or si3n4	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:10
L12	1024	5 and 6 and 8 and 9	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:10
L13	15004	sti or (shallow near2 trench)	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:12
L14	227	12 and 13 and 10 and 11	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:15
L15	4736	(angle or oblique\$2 or slant or degree\$1 or inclin\$5) near3 2	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:16

L16	39	14 and 15	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2004/12/09 14:16
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